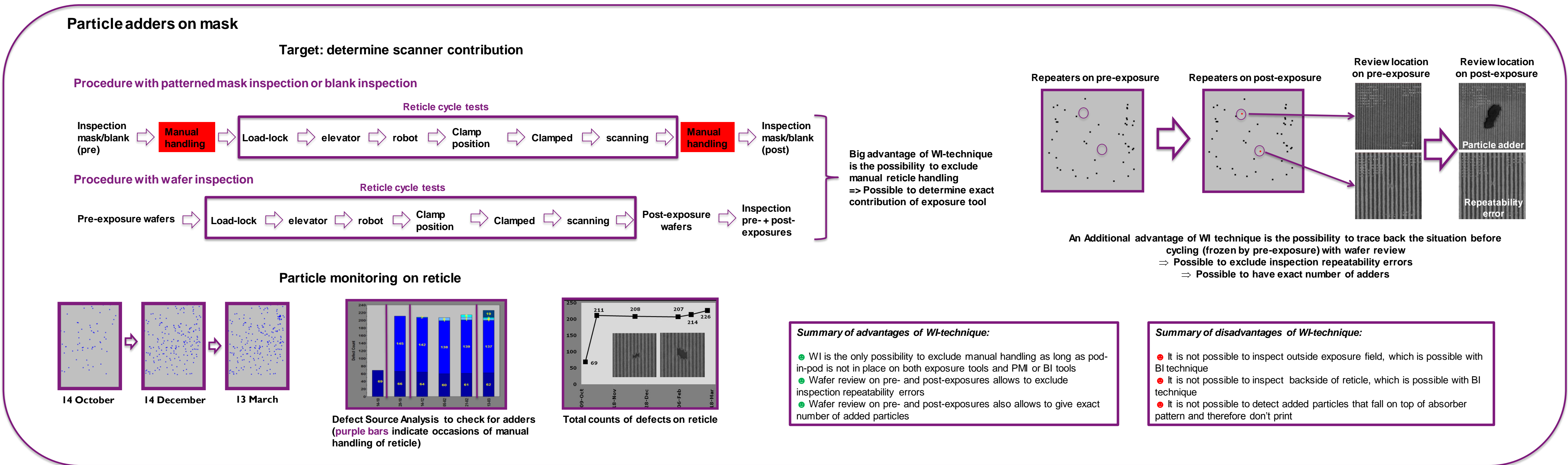
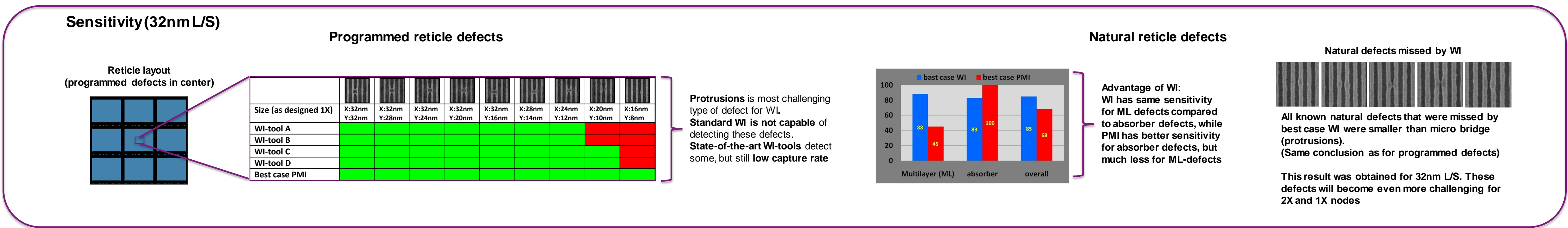
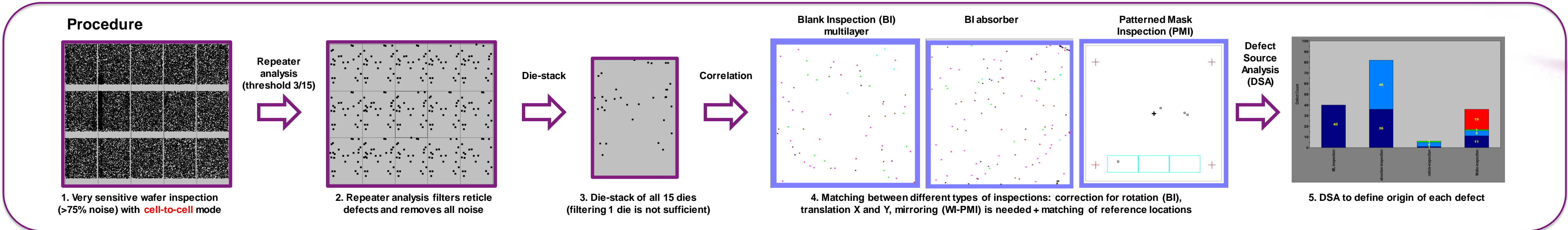


# THE USE OF OPTICAL WAFER INSPECTION TO QUALIFY EUV MASK DEFECTS AND PROCESS DEFECTS: LIMITATIONS AND ADVANTAGES OF THIS TECHNIQUE

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## RETICLE DEFECTS



## PROCESS DEFECTS

